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| APPLICATION NO. | FILING DATE | FIRST NAMED INVENTOR | ATTORNEY DOCKET NO. | CONFIRMATION NO. | |
|---|-------------|----------------------|-------------------------|------------------|--|
| 10/804,353 | 03/18/2004 | Robert Rozbicki | NOVLP024X2/NVLS-2852 | 9231 | |
| 22434 7590 10/03/2005 | | | EXAMINER | | |
| BEYER WEAVER & THOMAS LLP P.O. BOX 70250 | | | GURLEY, LYNNE ANN | | |
| OAKLAND, CA 94612-0250 | | | ART UNIT | PAPER NUMBER | |
| • | | | 2812 | | |
| | | | DATE MAILED: 10/03/2005 | | |

Please find below and/or attached an Office communication concerning this application or proceeding.

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|--|--|--|---|----|
| | | Application No. | Applicant(s) | - |
| | | 10/804,353 | ROZBICKI ET AL. | |
| | Office Action Summary | Examiner | Art Unit | |
| | | Lynne A. Gurley | 2812 | |
| Period fo | The MAILING DATE of this communication app or Reply | pears on the cover sheet with the | correspondence address | |
| WHIC - Exte after - If NC - Failu Any | ORTENED STATUTORY PERIOD FOR REPLY CHEVER IS LONGER, FROM THE MAILING DATE OF THE MONTHS AT THE MONTH OF THE MONTHS AT THE MONTH OF TH | ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be to the state of the state | N. imely filed n the mailing date of this communication. ED (35 U.S.C. § 133). | |
| Status | | , | | |
| 1)🖾 | Responsive to communication(s) filed on 18 M | larch 2004. | | |
| 2a) <u></u> ☐ | This action is FINAL . 2b)⊠ This | action is non-final. | | |
| 3)[| Since this application is in condition for allowar | | | |
| | closed in accordance with the practice under E | Ex parte Quayle, 1935 C.D. 11, 4 | I53 O.G. 213. | |
| Disposit | ion of Claims | | | |
| 4)⊠ 5)□ 6)⊠ 7)□ | Claim(s) 1-23 is/are pending in the application 4a) Of the above claim(s) is/are withdraw Claim(s) is/are allowed. Claim(s) 1-23 is/are rejected. Claim(s) is/are objected to. Claim(s) are subject to restriction and/o | wn from consideration. | • | |
| Applicat | ion Papers | | | |
| 9)[| The specification is objected to by the Examine | er. | | |
| 10) | The drawing(s) filed on is/are: a) acc | epted or b)□ objected to by the | Examiner. | |
| | Applicant may not request that any objection to the | | | |
| 11) | Replacement drawing sheet(s) including the correct The oath or declaration is objected to by the Ex | | | |
| , | under 35 U.S.C. § 119 | | | |
| 12) <u>□</u> a) | Acknowledgment is made of a claim for foreign All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority document application from the International Burear | s have been received. s have been received in Applica rity documents have been recei u (PCT Rule 17.2(a)). | ition No ved in this National Stage | |
| * (| See the attached detailed Office action for a list | or the certified copies not receive | Small 11 | |
| 2) Noti | ce of References Cited (PTO-892) ce of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) | 4) Interview Summa Paper No(s)/Mail 5) Notice of Informal | | |
| Pap | er No(s)/Mail Date <u>3/18/04</u> . | 6) | | |

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DETAILED ACTION

Specification

1. The specification has not been checked to the extent necessary to determine the presence of all possible minor errors. Applicant's cooperation is requested in correcting any errors of which applicant may become aware in the specification.

Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 3. Claims 1-2, 6-8, 16-19, 21-22 are rejected under 35 U.S.C. 102(e) as being anticipated by Gopalraja et al. (US 6,274,008, dated 8/14/01, filed 10/2/00).
- 4. Gopalraja shows the method as claimed, in figures 14-16, as: (a) etching the bottoms of recessed features (218/212; figs. 14-15) on a surface of the substrate 210 to clean at least part of an underlying metal while simultaneously depositing a first portion of a diffusion barrier on at least sidewalls of recessed features (fig. 15); (b) depositing a second portion of the diffusion barrier 228, which covers at least the bottoms of the recessed features; and (c) depositing the metal conductive layer (column 14, lines 18-30) over the surface of the substrate. Preclean is not necessary (column 5, lines 1-4).

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5. Claims 1-2, 6-8, 16-17 and 21-22 are rejected under 35 U.S.C. 102(e) as being anticipated by Hashim et al. (US 6,287,977, dated 9/11/01, filed 7/31/98).

6. Hashim shows the method as claimed in figures 1-10 and corresponding text, with emphasis on figures 4A-4D, as: (a) etching the bottoms of recessed features (55/57; fig. 4A) on a surface of the substrate to clean at least part of an underlying metal while simultaneously depositing a first portion of a diffusion barrier on at least sidewalls of recessed features (fig. 4B); (b) depositing a second portion of the diffusion barrier 61, which covers at least the bottoms of the recessed features; and (c) depositing the metal conductive layer (57b) over the surface of the substrate.

Claim Rejections - 35 USC § 103

- 7. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 8. The factual inquiries set forth in *Graham* v. *John Deere Co.*, 383 U.S. 1, 148 USPQ 459 (1966), that are applied for establishing a background for determining obviousness under 35 U.S.C. 103(a) are summarized as follows:
 - 1. Determining the scope and contents of the prior art.
 - 2. Ascertaining the differences between the prior art and the claims at issue.
 - 3. Resolving the level of ordinary skill in the pertinent art.
 - 4. Considering objective evidence present in the application indicating obviousness or nonobviousness.

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- 9. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).
- 10. Claims 3-5, 9-15, 20 and 23 are rejected under 35 U.S.C. 103(a) as being unpatentable over Gopalraja et al. (US 6,274,008, dated 8/14/01, filed 10/2/00).
- 11. Gopalraja shows the method substantially as claimed, and as described in the previous paragraphs.
- 12. Gopalraja lacks anticipation only in not teaching an additional etching step for the barrier layer; a degas operation prior to (a); aspect ratios; a hollow cathode magnetron processing chamber; heating while degassing; depth of the etching of the bottom of the recessed features; etch-to-deposition ratio; thicknesses; claimed power ranges; and flow rates.
- 13. It would have been obvious to one of ordinary skill in the art to have had a degas operation prior to (a); the claimed aspect ratios; a hollow cathode magnetron processing chamber; heating while degassing; the claimed depth of the etching of the bottom of the recessed features; the claimed etch-to-deposition ratio; thicknesses; claimed power ranges; and flow rates, in the method of Gopalraja, with the motivation that a magnetron device is disclosed (column 1, lines 59-67; column 4, lines 48-53; column 6), so that the specific type of magnetron processing

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apparatus would be a matter of design choice; and, with the motivation that the additional claimed ranges and features are parameters of optimization to one of ordinary skill in the art.

14. Claims 3-5, 9-15, 18-20 and 23 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hashim et al. (US 6,287,977, dated 9/11/01, filed 7/31/98).

Hashim shows the method substantially as claimed, and as described in the previous paragraphs.

15. Hashim lacks anticipation only in not teaching an additional etching step for the barrier layer; a degas operation prior to (a); aspect ratios; a hollow cathode magnetron processing chamber; heating while degassing; depth of the etching of the bottom of the recessed features; etch-to-deposition ratio; thicknesses; claimed power ranges; and flow rates.

It would have been obvious to one of ordinary skill in the art to have had a degas operation prior to (a); the claimed aspect ratios; a hollow cathode magnetron processing chamber; heating while degassing; the claimed depth of the etching of the bottom of the recessed features; the claimed etch-to-deposition ratio; thicknesses; claimed power ranges; and flow rates, in the method of Hashim, with the motivation that a sputtering chamber is disclosed, so that the specific type of sputtering apparatus, including a magnetron sputtering apparatus, would be a matter of design choice; and, with the motivation that degassing is disclosed and the additional claimed ranges and features are parameters of optimization to one of ordinary skill in the art.

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Conclusion

16. The prior art made of record and not relied upon is considered pertinent to applicant's

disclosure. See the PTO Form 892.

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Lynne A. Gurley whose telephone number is 571-272-1670. The

examiner can normally be reached on M-F 7:30-4:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Michael Lebentritt can be reached on 571-272-1873. The fax phone number for the

organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent

Application Information Retrieval (PAIR) system. Status information for published applications

may be obtained from either Private PAIR or Public PAIR. Status information for unpublished

applications is available through Private PAIR only. For more information about the PAIR

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR

system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Lynne A. Gurley

Primary Patent Examiner

gue A. Gurly

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LAG

September 29, 2005